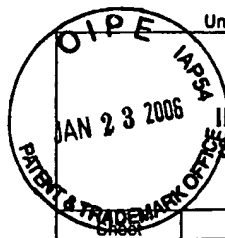


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Complete If Known

Application Number	10/847,985
Filing Date	August 28, 2003
First Named Inventor	Patricia Beauregard Smith, et al.
Group Art Unit	1746
Examiner Name	Zelnab El-Arini
Attorney Docket No.	TI-33260

U.S. PATENT DOCUMENTS

Exam. Initials [*]	Cite No. ¹	U.S. Patent Document		Name of Patentee or Applicant of Cited Doc.	Date of Pub. of Cited Doc. (mm-dd-yyyy)	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code ² (if known)			
ZE	AA	2003/0104320	A1	Nguyen et al.	08/05/2003	
	AB	2003/0008518	A1	Chang et al.	01/09/2003	
	AC	6,107,202		Chiu et al.	08/22/2000	
	AD	6,100,183		Lu et al.	08/08/2000	
	AE	5,798,323		Honda et al.	08/25/1998	
ZE	AF	5,843,407		Chang	07/01/1997	
	AG					
	AH					
	AI					
	AJ					

FOREIGN PATENT DOCUMENTS

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		Office ³	Number ⁴	Kind Code ² (if known)				
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NON PATENT LITERATURE DOCUMENTS

Exam. Initials [*]	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
ZE	CA	OKUDA, Seichiro, et al., "New Dry Tool after Cleaning of Low-k Dielectrics," <i>Solid State Phenomena</i> , Vol. 92, 2003, pp. 287-291, Proceedings of Ultra Clean Processing of Silicon Surfaces Conference, April 15, 2003, Diffusion and Defect Data, Solid State Data, Part B, Vaduz, LI, September 2003.	
ZE	CB	YANG, S.C., et al., "Process Optimization of Hydrogen Silsesquioxane (HSQ) Via Etch for 0.18um Technology and Beyond," <i>Advanced Metallization Conference 1999</i> , Orlando, Florida, September 28-30, 1999, pp. 455-459.	
	CC		
	CD		
	CE		
	CF		
	CG		
	CH		
	CI		
	CJ		

Examiner Signature	EL-Arini	Date Considered	3/10/06
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